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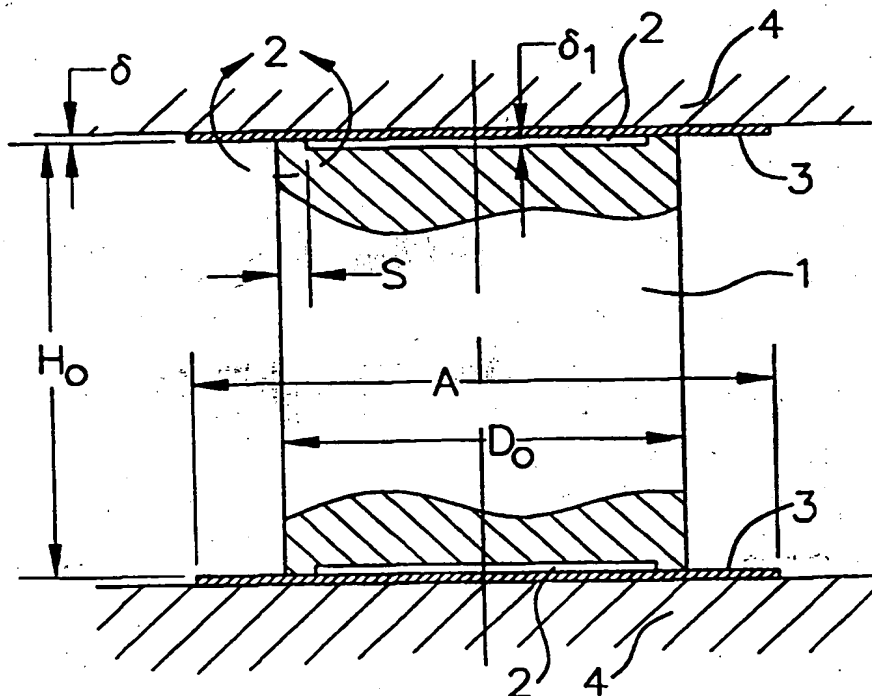
INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

<p>(51) International Patent Classification: C21D 8/00, C22C 5/02, 5/04, 5/06, 9/00, 14/00, 19/00, 21/00, 27/00</p>	<p>A1</p>	<p>(11) International Publication Number: WO 99/02743</p> <p>(43) International Publication Date: 21 January 1999 (21.01.99)</p>
<p>(21) International Application Number: PCT/US98/13447</p> <p>(22) International Filing Date: 26 June 1998 (26.06.98)</p> <p>(30) Priority Data: 60/052,218 11 July 1997 (11.07.97) US 09/098,761 17 June 1998 (17.06.98) US</p> <p>(71) Applicant: JOHNSON MATTHEY ELECTRONICS, INC. [US/US]; East 15128 Euclid Avenue, Spokane, WA 99216 (US).</p> <p>(72) Inventor: SEGAL, Vladimir; 1906 South Sonora Drive, Veradale, WA 99037 (US).</p> <p>(74) Agent: GIOIA, Vincent, G.; Christie, Parker & Hale, LLP, P.O. Box 7068, Pasadena, CA 91109-7068 (US).</p>		<p>(81) Designated States: CN, DE, GB, JP, KR, SE, SG, European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE).</p> <p>Published With international search report.</p>

(54) Title: METAL ARTICLE WITH FINE UNIFORM STRUCTURES AND TEXTURES AND PROCESS OF MAKING SAME

(57) Abstract

Described is the production of a metal article with fine metallurgical structure and texture by a process that includes forging and rolling and control of the forging and rolling conditions. Also described is a metal article with a minimum of statically crystallized grain size difference in grain size at any location of less than about $\pm 3\%$, as well as a dispersion in orientation content ratio of textures of less than about $\pm 4\%$ at any location.



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METAL ARTICLE WITH FINE UNIFORM STRUCTURES AND TEXTURES AND PROCESS OF MAKING SAME

BACKGROUND

The invention relates to metal articles with fine uniform structures and textures and methods of making such articles. In particular, metal articles of type described are especially useful as sputtering targets.

Sputtering targets of high purity metals and alloys are widely used in electronics and semiconductor industries for sputtering thin films. It is desirable to obtain large size targets.

SUMMARY OF THE INVENTION

In accordance with one embodiment of the invention there is provided a process for producing a metal article, such as a sputtering target, with fine metallurgical structure and texture comprising:

- 1) providing a metal billet;
- 2) heating the billet to a forging temperature below the recrystallization temperature of the metal;
- 3) applying a solid lubricant between the ends of the billet to be forged and press plates of a forging machine in which the billet is to be forged to reduce the friction during forging;
- 4) forging the billet to a desired billet thickness with about 70% to 90% reduction;
- 5) bringing the forged billet to about room temperature;
- 6) rolling the billet to plate with a reduction in thickness per rolling pass sufficient to provide near uniform strain distribution; and
- 7) recrystallization annealing the plate.

It is also advantageous to machine shallow pockets in both ends of the billet ends prior to applying the solid lubricant of sufficient thickness. Preferably, the billet is forged at a temperature below the minimum temperature of static recrystallization and then rolled and annealed at a time and temperature to provide the beginning stage of static recrystallization.

The rolling reduction per pass is desirably in accordance with a relationship of the minimum reduction per pass, the roll diameter and the desire billet thickness after forging. Generally, the reduction per pass during rolling is about 10% to 20% per pass.

Another embodiment the invention comprises a metal article, such as a sputtering target, having a near to minimum of statically crystallized grain size, a difference in grain size at any location of less than about $\pm 3\%$ and a dispersion in orientation content ratio of texture of less than about $\pm 4^\circ$.

The present invention can be applied to different metals and alloys that display good

ductility and workability at temperatures below corresponding temperatures of static recrystallization. Among metals with which the invention can be applied are Al, Ti, Ta, Cu, Nb, Ni, Mo, Au, Ag, Re, Pt and other metals, as well as their alloys. One embodiment of the method comprises the steps of processing an ingot to a semi-finished billet, including, for example, melting, ingot casting, homogenizing/solutionizing heat treatment, hot working to break down the cast structure, and billet preparation followed by billet shaping and thermomechanical treatment to fabricate a product, for example a sputtering target, and refine the metallurgical structure and produce a desired texture. By one embodiment of the process of the invention, cold/warm working and annealing are used to develop extremely fine, uniform structures and strong, uniform textures that result in improvement in performance of sputtering targets.

DESCRIPTION OF THE DRAWINGS

FIG. 1 is a billet-film lubricant assembly at the beginning of upsetting;

FIG. 2 shows a sectional view "C" of FIG. 1 during upsetting;

FIG. 3 shows the beginning of rolling for long cylindrical billets;

FIG. 4 shows the beginning of rolling for short cylindrical billets;

FIG. 5 is a graph relating grain size and temperature for recrystallized structures showing effect of recrystallization annealing on grain size of pure Ti alloy after frictionless forging/rolling;

FIG. 6A is the microstructure of pure Ti after frictionless forging/rolling and annealing at 375°C, 2 hours (x200 magnification);

FIG. 6B is the microstructure of pure Ti after frictionless forging/rolling and annealing at 675°C, 2 hours (x200 magnification);

FIG. 7A shows the dispersion in grain size of pure Ti after frictionless forging/rolling and annealing at 375°C, 2 hours;

FIG. 7B shows the dispersion in grain size of pure Ti after frictionless forging/rolling and annealing at 675°C, 2 hours; and

FIG. 8 shows the effect of annealing temperature on texture (x-ray intensity ratios) of pure titanium after frictionless forging/rolling processing.

DETAILED DESCRIPTION

To optimize thermomechanical treatment, it is desirable to attain intensive and uniform strains before recrystallization annealing. Typically, targets are thin discs fabricated from a single billet processed by rolling or upsetting-forging operations. In both cases, an original billet length (H_0) is reduced to a final thickness (h) and an average strain may be calculated by the formula:

$$(1) \quad \epsilon = (1 - h/H_0) 100\% = [1 - (M/M_0)^{2/3}] 100\%$$

where $M_o = H_o/D_o$ and $M = h/d$ are height-to-diameter ratios of the original billet and the worked product, correspondingly. The final ratio (M) is prescribed by the desired target shape and is usually in the range of from $M = 0.07$ to $M = 0.3$, while the original billet ratio M_o may be in the range of from about 1.0 to 0.5 and yields limits of strain shown in previously described equation (1) as follows:

$$(2) \quad 73\% < \epsilon < 89\%$$

Strain in equation(2) is high enough to optimize static recrystallization only for thin targets. But even for these targets non-uniformity in strain distribution through a billet volume may significantly reduce the amount strain in some areas. Also, demands on capacity of a forging press or rolling mill necessary to provide strains of equation (2) above for large target billets may be too high for some applications. Therefore, there may be restrictions on attainable strains by rolling or forging operations.

Rolling is most suitable for processing to produce thin and large targets. But the original billet ratio (M_o) advantageously should be less than 1, otherwise the end effect during rolling of long cylindrical billets develops very strong non-uniformity in strain distribution. In addition, to provide near uniform strains even for thin billets, the roll diameter advantageously should be significantly larger than the billet thickness and the number of reductions per pass can influence the result. Because of the foregoing, rolled billets may have concave-like shapes with maximum strain at contact surfaces and minimum strains at the middle billet section that are not sufficient to optimize recrystallization and develop most useful structures. Recently published Japan Patent No 08-269701 describes a titanium target manufactured by intensive cold rolling of sheet from stock and low temperature annealing. However, this technology cannot be applied to plates and although fine grain size is described for some target parts, the Japanese patent data shows large deviation in grain diameters.

Strain non-uniformity from forging is much stronger than for rolling. Because of contact friction, extensive "dead metal" zones are present at the central billet area. This results in low strains inside these zones and high pressure and load for thin billets. Upsetting bulk targets from a large billet with a large thickness-to-diameter ratio requires very powerful presses and expensive tools but cannot produce products with uniform grain diameters. That is why the forging operation is mostly used for hot breakdown of cast ingots only.

One attempt to overcome these problems is described in Japanese Patent No 08-232061. The patent describes a combination of forging and rolling for titanium targets at temperatures below the temperature of phase transformation. The process uses a temperature below the phase transformation temperature but well above the temperature of static recrystallization for heavy

worked materials. As a result, the process cannot optimize recrystallization and develop very fine and uniform structures/textures.

In contrast to the foregoing, the present invention includes:

1) performing the forging step as frictionless upsetting to provide stress-strain uniformity and intensive working without material cracking and press over-loading; and

2) performing the forging step at temperatures below the minimum temperature of static recrystallization for corresponding conditions to provide the finest and most uniform structures/textures. The steps of forging, rolling and annealing can be optimized to provide cost-effective processing and target performance.

Referring to FIG. 1, the original billet (1) has a cylindrical shape and a volume and length-to-diameter ratio M_o . Two shallow pockets (2) are fabricated at the billet ends before upsetting. Cold upsetting is preferable, but in some cases preheating of the billet and tool to a temperature below the temperature of static recrystallization may be used to reduce working pressure and load. Two thin sheets of solid lubricant (3) are placed between the billet end and forging plate (4) mounted in a press. It has been found that best results are obtained with lubricant polymers that exhibit visco-elastic behavior at working conditions, such as polyethylene, polytetrafluoroethylene or polyurethane.

As can be seen in FIGS. 1 and 2, depending on the billet diameter D_o , film thickness (δ) is varied from about 0.5 mm to 2.5 mm while film size (A) should exceed D_o . Pocket depth (δ_o) is advantageously slightly less than film thickness (δ) and pocket borders (5) have a width "S" from about 5 mm to 20 mm.

In accordance with the present invention, visco-elastic polymer film is used to entirely separate the billet and tool. During upsetting, the polymer fills the pockets and flows into contact with the billet. Some excess of polymer flows out from the pockets (FIG. 2) and provides low positive friction in the flow direction along billet ends, thus eliminating "dead metal" zones and improving billet stability. It has been found that with the invention the original billet ratio (M_o) may be as large as $M_o = 1.5$, and the polymer lubricant film enables partial reductions of up to $\epsilon - 75\%$. Because of increase of the original billet ratio M_o to 1.5, the limits for attainable strain (see equation (1)) are much better than (2)

$$(3) \quad 87\% < \epsilon < 92\%$$

that in conjunction with uniform strain distribution allows one to optimize recrystallization in most cases. Also, thin billet after forging (up to $M=0.16$) provides the best conditions for following rolling.

The preliminary forged billet is rolled for further reduction of thickness. Cold or warm

rolling may be used. Rolling may be performed in two or four mutually perpendicular directions to produce a product with a circle-like shape. It is important to provide the most uniform strain distribution during rolling by controlling roll diameter-to-billet thickness ratios (ϕ/H), billet thickness-to-diameter ratio (M) and reductions per pass. An important aspect is to prevent buckling along the free surface (2) of a cylindrical billet (1) at the beginning of rolling (FIG. 3). It has been found that buckling area (T) is approximately equal to a billet-roll contact length (L), and buckling is eliminated if contact length exceeds a billet thickness h_1 after the first pass (FIG. 4). In other words, if $L > H$, then

$$(4) \quad \phi/H \geq \frac{4(1-\epsilon)^2 + \epsilon^2}{2\epsilon}$$

where ϕ is the roll diameter, $\epsilon = (1-h/H)$ 100% is rolling reduction per pass. Calculations with formula (4) for different reductions are shown in Table 1.

Table 1

ϵ	5%	10%	15%	20%	25%
ϕ/H	36	16	9.7	6.5	4.6

As can be seen, at an average reduction of 15% or less, the roll diameter should be at least about 10 times (9.7 in Table 1) as large as the cylindrical billet thickness. On the other hand, use of thin billets for rolling without upsetting reduces possible reductions (1). Conventional target rolling suffer from both disadvantages, that is, non-uniform and low reductions are equally unacceptable to optimize structure. In the present invention high ratios of roll diameter-to-billet thickness (ϕ/H) are provided by preliminary billet upsetting to the necessary thickness (H). Simultaneously the upsetting operation provides a pre-rolling billet ratio (m) of less than about 0.3 that is useful to attain uniform rolling reductions along a billet. Partial rolling reductions from about 10% to 20% per pass are also useful for near uniform strain distribution in the final product. Rolling reductions lower than about 10% develop higher strains at billet surfaces while reduction more than about 18% develop higher strains at billet middle section. All these parameters define the best embodiments for performing upsetting and rolling for targets for optimum results.

The last step in target processing is recrystallization annealing. For many metals and alloys, strains from equation (3) are enough to optimize static recrystallization. To attain this goal, first the lowest temperature necessary to start static recrystallization, and then the shortest time necessary to complete that at all billet volume should be determined. Corresponding structures have the minimum grain sizes and the lowest dispersions of grain diameters inside

each local area. As the present method also provides uniform strains at any part of the billet, the minimum temperature of static recrystallization may be realized as the optimal temperature for the whole billet at the shortest time. This results in very fine and uniform structures and strong, uniform texture for the target produced.

Another embodiment of the invention is preforming forging in a few steps with successive decrease a billet thickness and resumption of film lubricant at each step. That way forging may be prolonged to low billet thickness without distortion of frictionless conditions and strain uniformity under relative low pressure and load. If forging is continued to the final target thickness without rolling, corresponding forging textures are provided for targets. Similarly, in the special cases rolling may be performed without forging with near uniform strain distribution in accordance with the invention.

The following example illustrates one embodiment of the invention.

High purity titanium was cast into an ingot of 300 mm diameter and hot worked by swaging at a temperature of 800 C to a rod diameter of 130 mm. Billets of 162 mm length were then cut from the 130 mm rod. Pockets of 120 mm diameter and 1 mm thickness were machined at billet ends. Billets were upset at a temperature of 350°C to a thickness of 54 mm. Teflon films of 150 x 150 mm² and thickness of 1.2 mm were used as lubricants for frictionless upsetting. Thereafter cold rolling with a roll diameter of 915 mm was performed in eight passes with partial reductions of 12% per pass along four directions under an angle of 45°.

Coupons across the thickness of the rolled billet were cut from central, mid-radius and external areas and annealed at different temperatures during 2 hours (h). Two planes of coupons, one near the surface and the second near the middle section, were investigated for structure and texture and photomicrographs thereof are shown in FIGS. 6A and 6B.

In another example, tantalum sputtering targets were made by the process described above. The composition of the resulting tantalum target is shown in Table 2, the target comprising 99.95% tantalum and balance as shown in the table.

Table 2

ELEMENT	TYPICAL	ELEMENT	TYPICAL
C	10	Ca	<5
O	15	Fe	15
N	15	Mg	<5
H	<5	Mn	40
K	0.001	Mo	40
Li	0.001	Nb	150
Na	0.001	Ni	<5
Al	<5	Si	15
B	2	Sn	<5
Cu	<5	Ti	5
Co	<5	W	25
Cr	<5	Zr	<5

Reported in ppm.

C, O, N and H by LECO analysis.

Na, Li and K by SIMS analysis.

Metallic elements by ICP (inductively Coupled Plasma).

FIG. 5 shows effect of annealing temperature on average grain size of titanium. The lowest temperature of static recrystallization is about 375°C. Corresponding very fine structure of average grain sizes of 6 micrometers demonstrates also low local dispersion of grain diameter and strong texture (1013) (FIG. 8) with orientation content ratio of 65% in the perpendicular direction to target surface. An increase of annealing temperature results in intensive grain growth and larger dispersion in grain size with only moderate strengthening of texture. The photomicrographs shown in FIGS. 6A and 6B show structures of pure Ti after frictionless forging/rolling and annealing at 375°C for 2 hours and annealing at 675°C for 2 hours, respectively. Analysis of structures and textures for different coupons did not detect a noticeable distinction at any target point. Dispersion in the average grain size at different target locations was less than about $\pm 3\%$ and dispersion in the orientation content ratio of textures was less than $\pm 4\%$ which, probably, corresponds to the accuracy of measurement methods. FIGS. 7A and 7B depict graphically the dispersion of grain size of pure Ti for the structures shown in FIGS. 6A and 6B, respectively.

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An important advantage of the invention is the production of very fine and uniform
structures and strong uniform textures at any point of a target which formerly could not be
5 attainable. The method provides targets with significant improvement in sputtering target
performance.

The following illustrate the features of one embodiment of the invention:

1) working a billet during thermomechanical processing by combining the frictionless
upset forging and rolling;

10 2) frictionless forging during upsetting operation that develops positive friction along
contact surfaces and increases process stability;

3) predetermine parameters of upsetting operation to increase accumulated strains,
reduce press capacity and enable effective rolling;

15 4) predetermine parameters of rolling conditions to enable near uniform strain
distribution and cylindrical shape (for sputtering targets) of the product;

5) using as the annealing temperature the lowest temperature of static recrystallization;
and

20 6) producing a sputtering target with very fine and uniform structures and uniform
strong textures not previously attainable.

WHAT IS CLAIMED IS:

1. A process for producing a metal article, such as a sputtering target, with fine metallurgical structure and texture comprising:
 - providing a metal billet;
 - heating the billet to a forging temperature below the recrystallization temperature of the metal;
 - applying a solid lubricant between the ends of the billet to be forged and press plates of a forging machine in which the billet is to be forged to reduce the friction during forging;
 - forging the billet to a desired billet thickness with about 70% to 90% reduction;
 - bringing the forged billet to about room temperature;
 - rolling the billet to plate with a reduction in thickness per rolling pass sufficient to provide near uniform strain distribution; and
 - recrystallization annealing the plate.
2. A process according to claim 1 wherein the billet is forged at a temperature below the minimum temperature of static recrystallization.
3. A process according to claim 1 wherein the billet is annealed at a time and temperature to provide the beginning stage of static recrystallization.
4. A process according to claim 1 wherein the solid lubricant comprises a film of a polymer that exhibits visco-elastic behavior at forging conditions.
5. A process according to claim 4 wherein the solid lubricant comprises polyethylene, polyurethane or polytetrafluoroethylene.
6. A process according to claim 1 wherein shallow pockets are machined at both billet ends prior to applying the solid lubricant.
7. A process according to claim 6 wherein the thickness of the solid lubricant applied to opposite ends of the billet prior to forging is slightly greater than the pocket depth.
8. A process according to claim 1 wherein the rolling reduction per pass is in accordance with the following relationship:

(4)
$$\phi/H \geq \frac{4(1-\epsilon)^2 + \epsilon^2}{2\epsilon}$$

where ϵ is the approximate minimum reduction per pass, ϕ is the roll diameter and H is the desired billet thickness after forging.

9. A process according to claim 1 wherein the billet is rolled to reduction of about 10% to 20% per pass.

10. A process according to claim 1 wherein the billet is forged in two or more forging steps with successive decrease in billet thickness and after applying solid lubricant before each forging step.

11. A process according to claim 1 wherein the metal billet comprises titanium.

12. A metal article, such as a sputtering target, having near to the minimum of statically recrystallized grain size, a difference in grain size at any location of less than about $\pm 3\%$ and a dispersion in orientation content ratio of textures of less than about $\pm 4\%$.

13. A metal article according to claim 12 comprising titanium.

14. A sputtering target according to claim 12.

FIG. 1

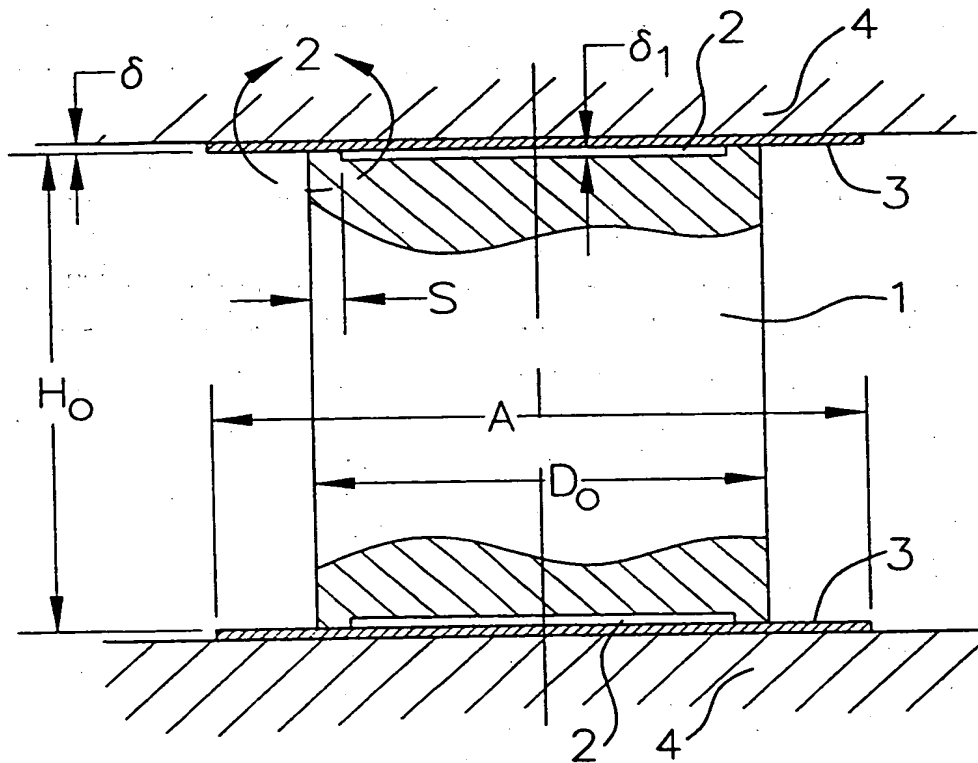


FIG. 2

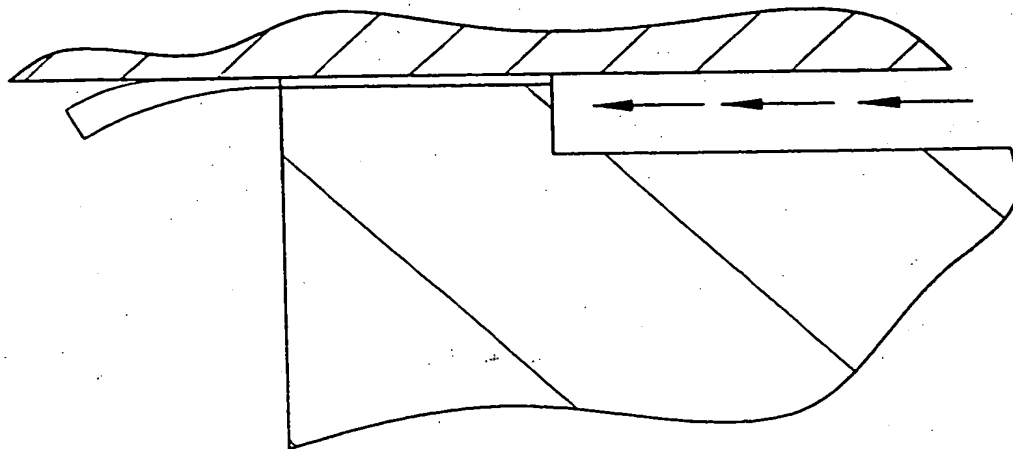


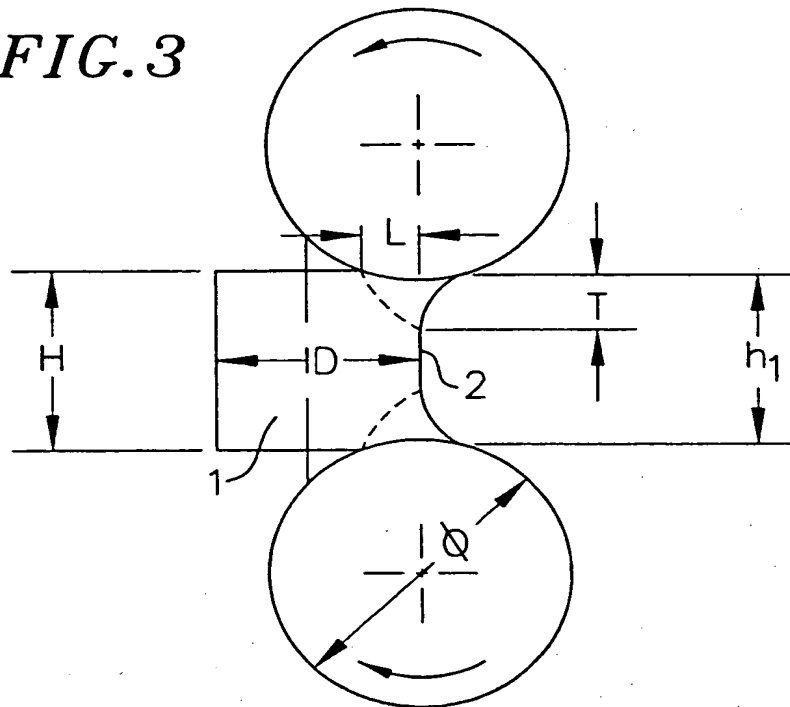
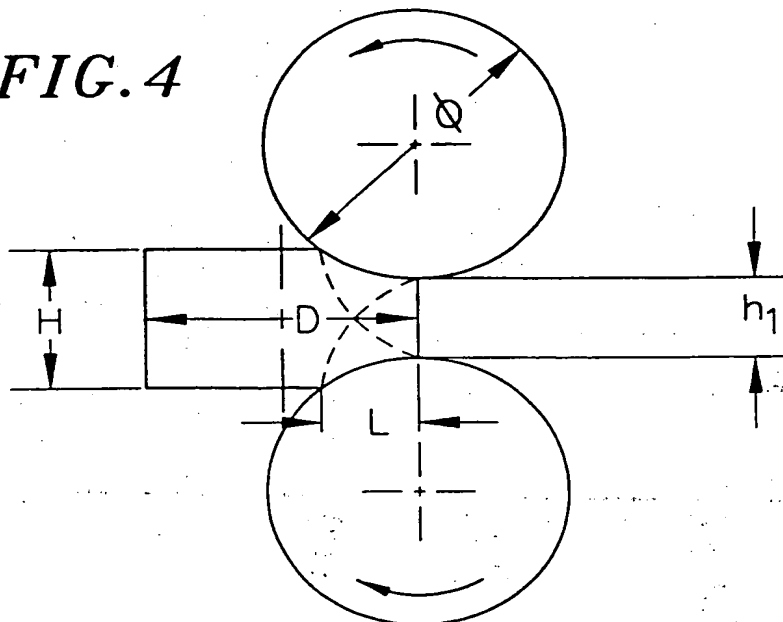
FIG. 3*FIG. 4*

FIG. 5

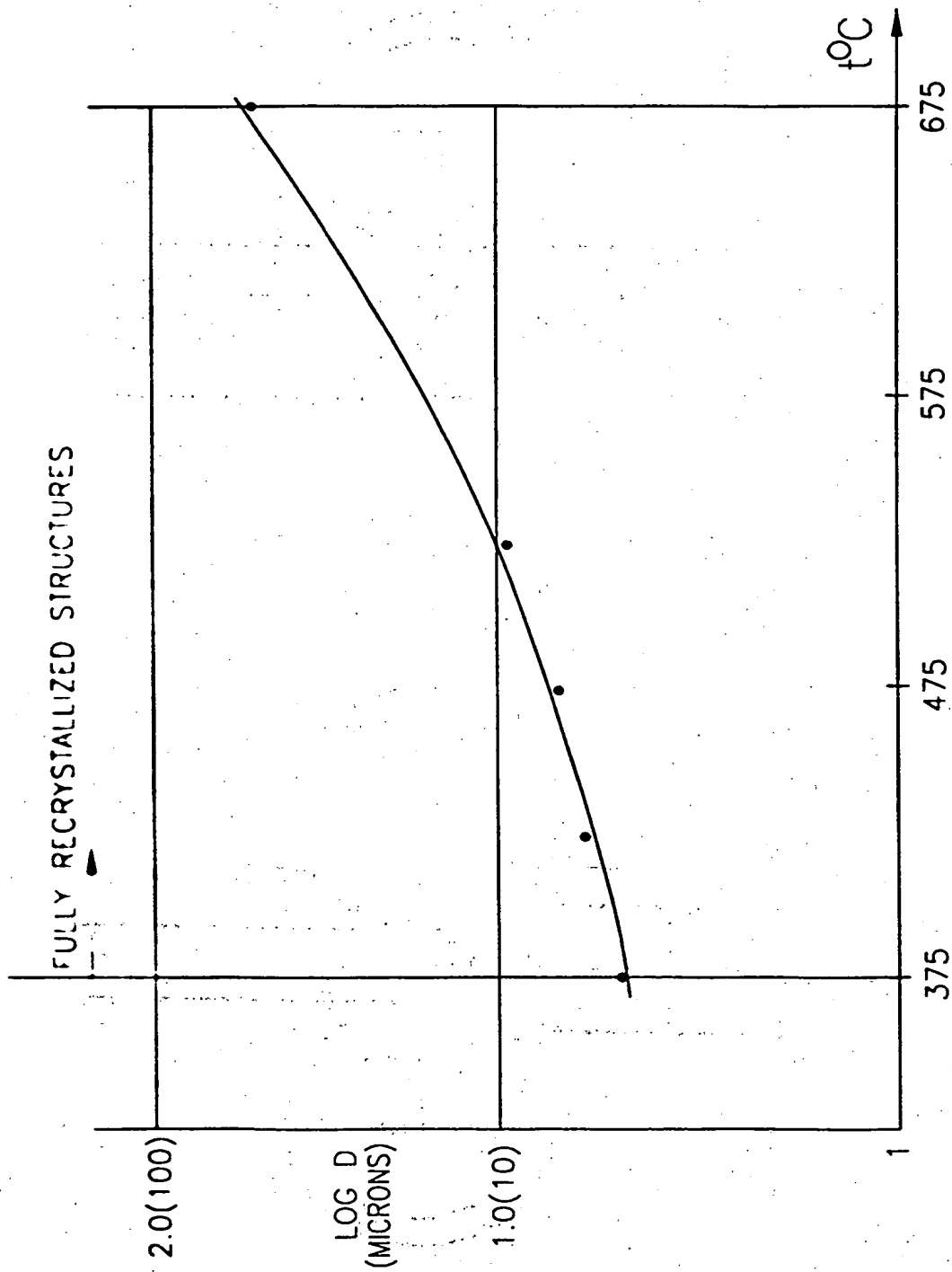
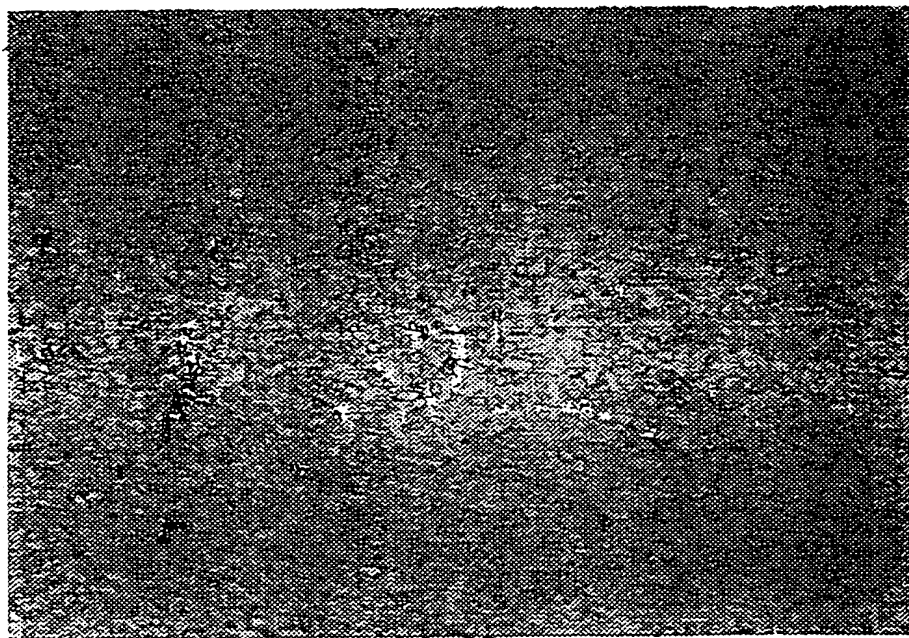
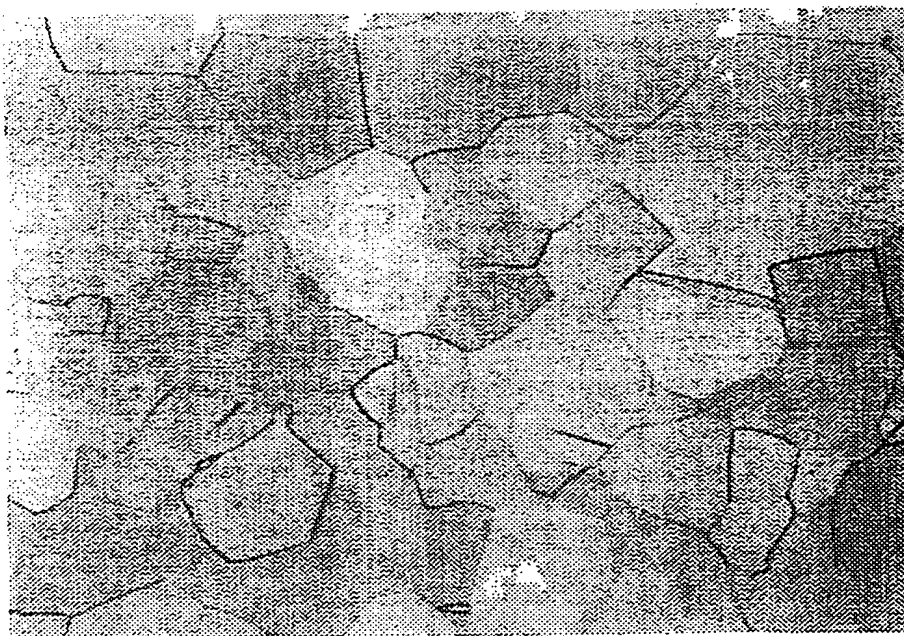


FIG. 6A

PURE Ti, ANNEALING T-RE
375°C, X200

FIG. 6B

PURE Ti, ANNEALING T-RE
675°C, X200

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FIG. 7A

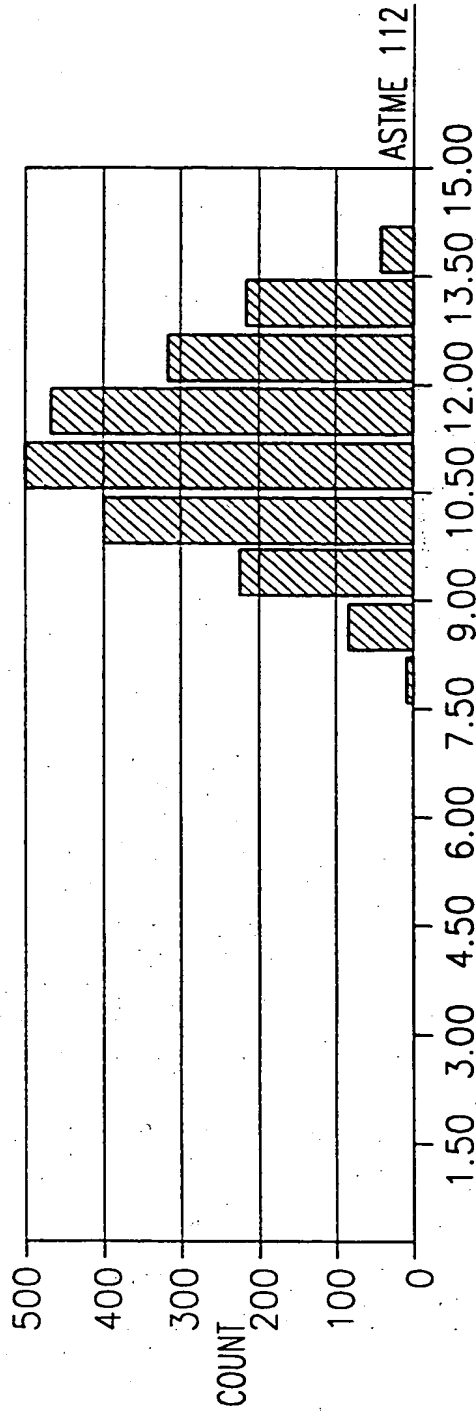


FIG. 7B

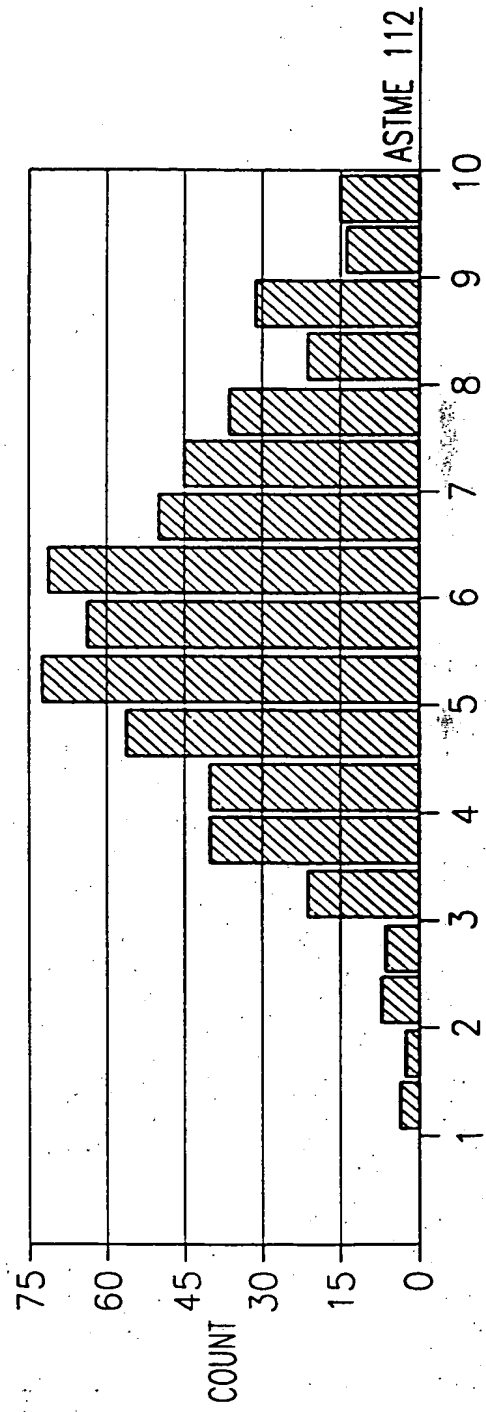
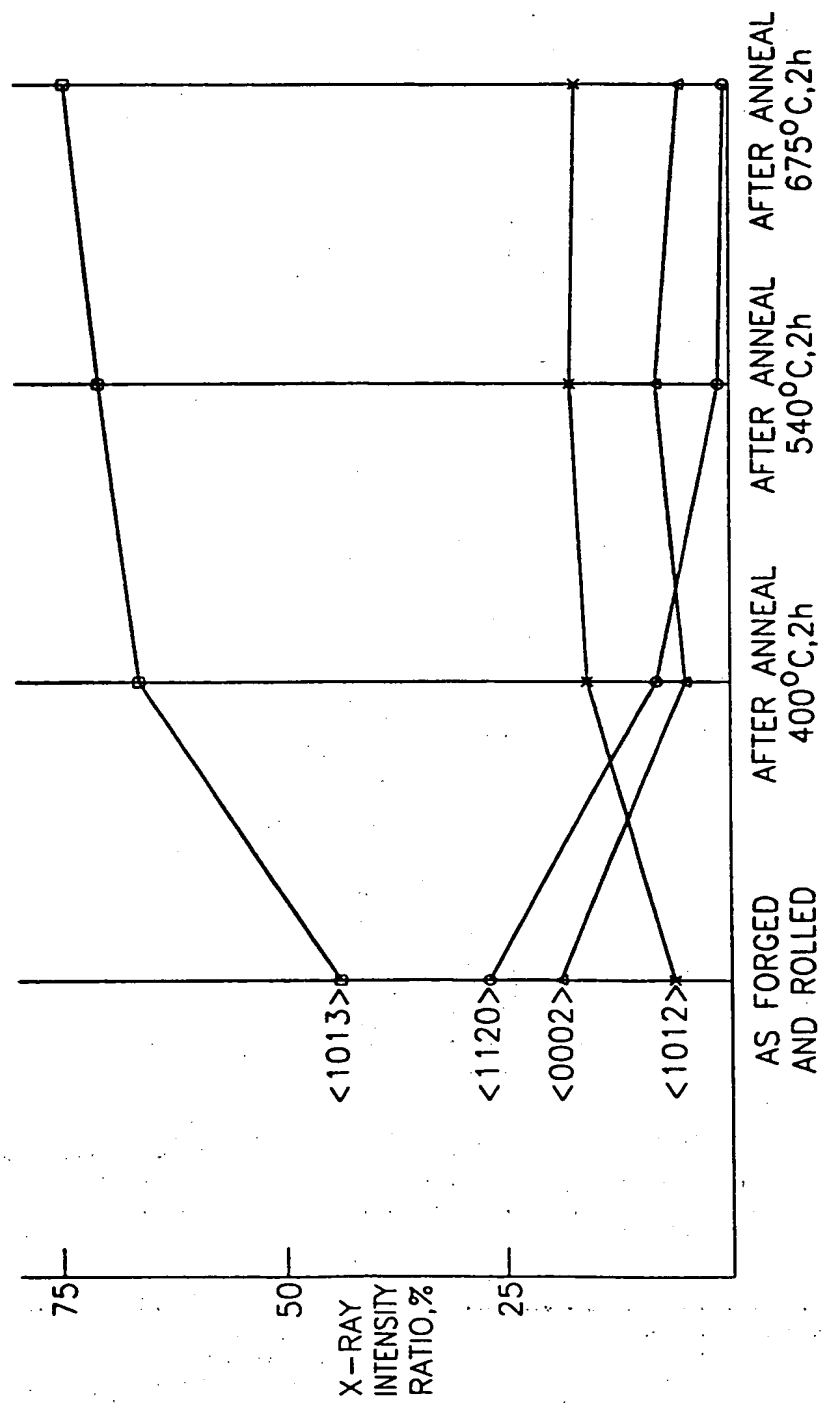


FIG. 8



INTERNATIONAL SEARCH REPORT

International application No.
PCT/US98/13447

A. CLASSIFICATION OF SUBJECT MATTER

IPC(6) : Please See Extra Sheet.

US CL : Please See Extra Sheet.

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

U.S. : 148/ 421, 422, 423, 426, 430, 668, 670, 676, 678, 681, 692, and 696

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched
none

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

APS

search terms: static, recrystallization, temperature and sputtering , forging, annealing

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	JP 6-10107 A (OSKA TITANIUM CO LTD) 18 January 1994, Table 1 on page 4.	1-14
A	JP 6-93400 A (NKK CORP) 05 April 1994, table on page 5.	1-14
A	JP 6-256919 A (SEIKO INSTR INC) 13 September 1994, english abstract.	1-14

☐ Further documents are listed in the continuation of Box C.
 ☐ See patent family annex.

* "A"	document defining the general state of the art which is not considered to be of particular relevance	* "T"	later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention
* "P"	earlier document published on or after the international filing date	* "X"	document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone
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Date of the actual completion of the international search

02 SEPTEMBER 1998

Date of mailing of the international search report

16 OCT 1998

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INTERNATIONAL SEARCH REPORT

International application No.
PCT/US98/13447

A. CLASSIFICATION OF SUBJECT MATTER:
IPC (6):

C21D 8/00; C22C 5/02, 5/04, 5/06, 9/00, 14/00, 19/00, 21/00, 27/00

A. CLASSIFICATION OF SUBJECT MATTER:
US CL :

148/ 421, 422, 423, 426, 430, 668, 670, 676, 678, 681, 692, and 696